## **LISTING OF THE CLAIMS:**

This listing of claims will replace all prior versions and listings of claims in the application:

Claim 1. (Cancelled).

Claim 2. (Previously presented) The process as claimed in claim 3, wherein the hermetic evaporation-coating glass layer is deposited by electron beam evaporation.

Claim 3. (Currently amended) A process for producing a coated substrate having a metallic surface, comprising:

producing at least one negatively structured first coating on the metallic surface;

depositing a borosilicate glass comprising aluminum oxide and alkali metal oxide components as an hermetic evaporation-coating glass layer on the first coating; [[and]]

at least partially removing the at least one negatively structured first coating and the hermetic evaporation-coating glass layer thereon, wherein the hermetic evaporation-coating glass layer is deposited with a thickness that is less than the thickness of the negatively structured first coating, and whereby the first coating remains accessible at side edges of structures of the negatively structured first coating after deposition of the hermetic evaporation-coating glass layer; and

at least partially uncovering the at least one negatively structured first coating.

Claim 4. (Previously presented) The process as claimed in claim 3, wherein the step of producing the at least one negatively structured first coating on the metallic surface comprises the step of uncovering regions of the metallic surface that are to be coated.

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Claim 5. (Previously presented) The process as claimed in claim 3, wherein the step of producing the at least one negatively structured first coating comprises the step of resist-coating or printing.

Claim 6. (Previously presented) The process as claimed in claim 3, wherein the step of at least partially removing the at least one negatively structured first coating comprises the step of lifting off regions of the hermetic evaporation-coating glass layer.

Claim 7. (Cancelled).

Claim 8. (Cancelled).

Claim 9. (Currently amended) The process as claimed in claim [[8]] 3, wherein the step of at least partially uncovering the at least one negatively structured first coating comprises the step of planarizing the metallic surface having the at least one negatively structured first coating and the hermetic evaporation-coating glass layer thereon.

Claim 10. (Currently amended) The process as claimed in claim [[8]] 3, wherein the step of partially uncovering the at least one negatively structured first coating comprises the step of mechanically removing material by a process selected from the group consisting of grinding, lapping, and polishing.

Claim 11. (Previously presented) The process as claimed in claim 3, wherein depositing the hermetic evaporation-coating glass layer comprises evaporation coating through a mask.

- Claim 12. (Previously presented) The process as claimed in claim 3, further comprising depositing at least two hermetic evaporation-coating glass layers on the metallic substrate.
- Claim 13. (Previously presented) The process as claimed in claim 12, wherein the at least two evaporation-coating glass layers comprise different compositions.
- Claim 14. (Previously presented) The process as claimed in claim 3, wherein the hermetic evaporation-coating glass layer is deposited with a thickness in a range from 0.01 µm to 1 mm.
- Claim 15. (Previously presented) The process as claimed in claim 3, wherein the hermetic evaporation-coating glass layer has a composition that is varied while being deposited.
- Claim 16. (Previously presented) The process as claimed in claim 3, wherein depositing the hermetic evaporation-coating glass layer comprises co-evaporating evaporation-coating material from at least two sources.
- Claim 17. (Previously presented) The process as claimed in claim 3, further comprising heating the metallic substrate during deposition of the hermetic evaporation-coating glass layer.
- Claim 18. (Previously presented) The process as claimed in claim 3, wherein depositing the hermetic evaporation-coating glass layer occurs at a pressure that is at most 10<sup>-4</sup> mbar.
- Claim 19. (Previously presented) The process as claimed in claim 3, further comprising structuring the hermetic evaporation-coating glass layer following the depositing operation.

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- Claim 20. (Previously presented) The process as claimed in claim 19, wherein structuring the hermetic evaporation-coating glass layer comprises local etching.
- Claim 21. (Previously presented) The process as claimed in claim 3, further comprising moving the metallic substrate with respect to a coating source during the depositing step.
- Claim 22. (Previously presented) The process as claimed in claim 3, wherein depositing the hermetic evaporation-coating glass layer comprises plasma ion assisted deposition (PIAD).

Claims 23-33. (Cancelled).

Claim 34. (Currently amended) A process for producing a coated substrate, comprising:

producing a negatively structured first coating on a metallic surface of a solid metal substrate;

depositing a borosilicate glass comprising aluminum oxide and alkali metal oxide components as an hermetic evaporation-coating glass layer on the negatively structured first coating; [[and]]

at least partially removing the negatively structured first coating and the hermetic evaporation-coating glass layer thereon, wherein the hermetic evaporation-coating glass layer is deposited with a thickness that is less than the thickness of the negatively structured first coating, and whereby the first coating remains accessible at side edges of structures of the negatively structured first coating after deposition of the hermetic evaporation-coating glass layer; and

at least partially uncovering the negatively structured first coating.

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Claim 35. (Previously presented) The process as claimed in claim 34, wherein the step of producing the negatively structured first coating on the metallic surface comprises the step of uncovering regions of the metallic surface that are to be coated with the hermetic evaporation-coating glass layer.

Claim 36. (Previously presented) The process as claimed in claim 34, wherein the step of at least partially removing the negatively structured first coating comprises the step of lifting off regions of the hermetic evaporation-coating glass layer.

Claim 37. (Cancelled).